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YS

**NONFERROUS METALS INDUSTRY STANDARD OF THE
PEOPLE'S REPUBLIC OF CHINA**

YS/T 1768-2025

**Determination of Impurities in the Surface of Graphite Products
Used in Polysilicon Production - Inductively-Coupled Plasma
Spectrometric Method
(English Translation)**

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What this standard covers

This standard specifies the inductively coupled plasma atomic emission spectrometry (ICP-AES) method for determining the content of elements such as sodium, magnesium, aluminum, potassium, calcium, chromium, iron, nickel, copper, zinc, arsenic, lead, manganese, boron, and phosphorus on the surface of graphite products used in polycrystalline silicon production. This document applies to the determination of the content of surface impurity elements in graphite products used in polycrystalline silicon production.

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